

The importance of ions and flux in pulsed laser deposition

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http://www.io.csic.es/Web_GPL/index.html

Pulsed laser deposition is acknowledged as a process that involves ions with kinetic energies that can be much higher than 200 eV and large flux of species arriving to the substrate. They lead to higher nucleation rates than when using more conventional deposition techniques and processes at the substrate such as sputtering of deposited material or sub-surface implantation with have impact on the film quality. Several examples of ablation of metals or alternate ablation of metals and oxide, will be given to illustrate these processes, correlating both plasma and film properties.